

LISTING OF CLAIMS

This listing of claims provided below will replace all prior versions and listings of claims in the application.

1. (Currently amended) A process for producing a poly(methyl methacrylate)-metal cluster composite, which comprises bringing poly(methyl methacrylate) into contact with a heavy metal compound under ultraviolet irradiation,

wherein the poly(methyl methacrylate) is brought into contact with the heavy metal compound in a non-oxidizing atmosphere at a temperature equal to or higher than the glass transition temperature of the poly(methyl methacrylate),

wherein the wavelength of the ultraviolet irradiation is from 250 to 350 nm, and

wherein the dose of the ultraviolet irradiation is from 0.1 to 2 J/cm².

2. (Currently amended) A process for producing a poly(methyl methacrylate)-metal cluster composite, which comprises bringing a poly(methyl methacrylate) basal plate having an ultraviolet-irradiated portion into contact with vapor of a heavy metal compound to form heavy metal nanoparticles on the ultraviolet-irradiated portion,

wherein the poly(methyl methacrylate) basal plate is brought into contact with vapor of the heavy metal compound in a non-oxidizing atmosphere at a temperature equal to or higher than the glass transition temperature of the poly(methyl methacrylate) basal plate,

wherein the ultraviolet-irradiated portion is formed in a predetermined pattern,

wherein the wavelength of the ultraviolet irradiation is from 250 to 350 nm, and

wherein the dose of the ultraviolet irradiation is from 0.1 to 2 J/cm².

3. (Original) The process for producing a poly(methyl methacrylate)-metal cluster composite according to claim 1 or 2, wherein the heavy metal compound is selected from acetylacetone complexes of palladium, cobalt or copper.

Claims 4-6. (Cancelled)

7. (Currently amended) The process for producing a poly(methyl methacrylate)-metal cluster composite according to claim [[6]] 2, wherein the predetermined pattern is formed by masking.

8. (Withdrawn) A patterning material which comprises a poly(methyl methacrylate)-metal cluster composite obtainable by the process according to claim 1 or 2.

9. (Currently amended) A method for patterning metal nanoparticles having a predetermined form on a poly(methyl methacrylate) basal plate, which comprises forming a masking portion having a predetermined form on the poly(methyl methacrylate) basal plate having an ultraviolet-irradiated portion, and then bringing the plate into contact with vapor of a heavy metal compound to form metal nanoparticles on a non-masking portion,

wherein the wavelength of the ultraviolet irradiation is from 250 to 350 nm, and

wherein the dose of the ultraviolet irradiation is from 0.1 to 2 J/cm².